

Customers

- Charles University in Prague, Group of Surface Science
- Materials Science Beamline, Synchrotron Elettra, Trieste, Italy
- Academy of Sciences of the Czech Republic, Prague
- National Institute for Materials Science Tsukuba, Japan
- Synchrotron SPring-8, Sayo, Japan
- *other Japan institutes and companies*: Meiji University, Kyushu University, Kyoto University, LEAP, Gene & Coherent Technologies, Nakayama Corporation
- Heinrich-Heine-Universität Düsseldorf, Germany
- Lehrstuhl fuer Physikalische Chemie II, Friedrich-Alexander-Universitaet Erlangen-Nuernberg
- Department of Solid State Physics, University of Lodz, Poland
- Department of Physics, University of California at Davis, USA
- ALS Synchrotron, Lawrence Berkeley National Laboratory, Berkeley, USA
- Chonbuk National University, Jeonju, South Korea
- etc...

Some papers where KoIXPD was used

This list excludes [my references](#)

- A. L. Yang, Y. Yamashita, M. Kobata, T. Matsushita, H. Yoshikawa et al., *Investigation of the near-surface structures of polar InN films by chemicalstate-discriminated hard X-ray photoelectron diffraction*, Appl. Phys. Lett. 102 (2013) 031914
- J.R. Williams, I. Piš, M. Kobata, A. Winkelmann, T. Matsushita, Y. Adachi, N. Ohashi, K. Kobayashi, *Observation and simulation of hard x ray photoelectron diffraction to determine polarity of polycrystalline zinc oxide films with rotation domains*, Journal of Applied Physics 111 (2012) 033525
- J.R. Williams, M. Kobata, I. Piš, E. Ikenaga, T. Sugiyama, K. Kobayashi, N. Ohashi, *Polarity determination of wurtzite-type crystals using hard x-ray photoelectron diffraction*, Surface Science 605 (2011) 1336
- M. Kobata, I. Piš, H. Iwai, H. Yamazui, H. Takahashi, M. Suzuki, H. Matsuda, H. Daimon, K. Kobayashi, *Development of the hard-X-ray angle Resolved X-ray Photoemission spectrometer for Laboratory use*, Analytic Sciences February 2010, Vol. 26
- I. Piš, M. Kobata, T. Matsushita, H. Nohira, K. Kobayashi, *Hard-X-ray Photoelectron Diffraction from Si(001) Covered by a 0–7-nm-Thick SiO₂ Layer*, Applied Physics Express 3 (2010) 056701
- Nemšák, S., Skála, T., Yoshitake, M., Prince, K.C., Matolín, V., *Depth profiling of ultra-thin alumina layers grown on Co(0001)*, Journal of Physics: Condensed Matter 25 (2013) 095004
- Nemšák, S., Skála, T., Yoshitake, M., Tsud, N., Prince, K.C., Matolín, V., *A photoelectron spectroscopy study of ultra-thin epitaxial alumina layers grown on Cu(111) surface*, Surface Science 604 (2010) 2073
- Nemšák, S., Skála, T., Yoshitake, M., Tsud, N., Kim, T., Yagyu, S., Matolín, V., *Growth of thin epitaxial alumina films onto Ni(111): an electron spectroscopy and diffraction study*, Surface and Interface Analysis 42 (2010) 1581
- Yoshitake, M., Blumentrit, P., Nemšák, S., *X-ray photoelectron spectroscopic study on interface bonding between Pt and Zn- and O-terminated ZnO*, Journal of Vacuum Science and Technology A 31 (2013) 020601
- Blumentrit, P., Yoshitake, M., Nemšák, S., Kim, T., Nagata, T., *XPS and UPS study on Band Alignment at Pt-Zn-terminated ZnO(0001) Interface*, Applied Surface Science 258 (2011) 780